

## ABSTRACT OF THE DISCLOSURE

5 A photolithography apparatus includes: an air supply line supplying  
an air to a chamber processing a wafer; a temperature and humidity  
adjuster provided to the air supply line; a temperature and humidity  
10 monitoring sensor sensing temperature and humidity internal to the  
chamber; and a controller connected to the temperature and humidity  
monitoring sensor and the temperature and humidity adjuster to control the  
temperature and humidity adjuster to supply the chamber via the air supply  
line with an air having the same temperature and humidity as those of the  
10 air in the chamber detected by the temperature and humidity monitoring  
sensor.